Title (en)

PROCESS FOR IMAGE-WISE MODIFYING THE SURFACE OF AN ETCHABLE SUPPORT AND MATERIAL SUITABLE THEREFOR COMPRISING A COLLOID LAYER CONTAINING POLYMERS WITH OXIME-ESTER GROUPS

Publication

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Application

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Priority

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Abstract (en)

[origin: US4202697A] A radiation-sensitive material is described that comprises a hydrophilic colloid layer containing a dispersed phase of at least one radiation sensitive polymer the polymer chain of which comprises units with side substituents containing oxime ester groups. Upon imagewise exposure to actinic radiation the polymer in the exposed areas reduces the permeability of the hydrophilic colloid layer for an etchant in the absence of any ethylenically unsaturated monomer. The layer having upon image-wise exposure to radiation image-wise differentiations in permeability for an etchant can be used as etch-resist, without needing a washing away step, to modify image-wise the surface of an element e.g. to produce printed circuits or printing forms.

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